

## Amendments to the Claims

This listing of claim will replace all prior versions and listings of claim in the application.

1. (previously presented) An integrated circuit device comprising:  
a bond pad structure including:
  - a conductive pad;
  - a first doped region of a first conductivity type disposed in a semiconductor substrate of a second conductivity type, wherein the first doped region is underlying and surrounding the conductive pad;
  - a conductive region of the first conductivity type, underlying and surrounding the conductive pad, disposed in the first doped region;
  - a first tap region spaced apart from and surrounding a substantial portion of the first doped region, wherein the first tap region is electrically coupled to a first supply voltage;
  - an output driver transistor having a drain region and a source region, wherein the drain region is electrically coupled to the conductive pad; and
  - a second tap region surrounding the output driver transistor, wherein the second tap region is electrically and physically coupled to a second supply voltage and the source region.
2. (previously presented) The integrated circuit device of claim 1 wherein the conductive pad includes a metal.
3. (previously presented) The integrated circuit device of claim 1 wherein the first tap region completely surrounds the first doped region, and wherein the first and second supply voltages are ground.
4. (previously presented) The integrated circuit device of claim 1 wherein the first tap region is a discontinuous region.
5. (previously presented) The integrated circuit device of claim 1 wherein a doping concentration of the first doped region is less than a doping concentration of the conductive region.

6. (previously presented) The integrated circuit device of claim 1 wherein the first tap region is a second doped region and the second tap region is a third doped region.

7. (previously presented) The integrated circuit device of claim 6 wherein the second doped region is of an opposite conductivity type than the first doped region.

8. (previously presented) The integrated circuit device of claim 6 wherein the third doped region is a P type doped region and the output driver transistor is an NMOS type transistor.

9. (previously presented) The integrated circuit device of claim 1 further including a tap region portion that is spaced apart from and surrounding the first doped region, wherein the tap region portion is decoupled from the first supply voltage to provide a predetermined resistance between the first doped region and the first supply voltage.

10. (previously presented) The integrated circuit device of claim 1 wherein a portion of the second tap region is integrated into the source region.

11. (previously presented) The integrated circuit device of claim 10 wherein the first tap region is a discontinuous region.

12. (currently amended) A bond pad for an integrated circuit device, the bond pad comprising:

a conductive bonding layer;

a first doped region of a conductivity type formed in a semiconductor substrate of a second conductivity type, wherein the doped region is underlying and surrounding the conductive bonding layer;

a conductive region of the first conductivity type disposed in the first doped region, wherein the conductive region is underlying and surrounding the conductive bonding layer and wherein the conductive region includes a surface area at least substantially equal to a surface area of the conductive bonding layer; and

a conductive tap region spaced apart from and surrounding at least a portion of the ~~first~~ doped region, wherein a portion of the conductive tap region is electrically coupled to a supply voltage.

13. (previously presented) The bond pad of claim 12 wherein the supply voltage is a ground voltage and the conductive bonding layer includes a metal.

14. (previously presented) The bond pad of claim 12 wherein the doping concentration of the doped region is less than the doping concentration of the conductive region.

15. (currently amended) The bond pad of claim 12 wherein the conductive tap region is doped to be of an opposite conductivity type than the ~~first~~ doped region.

16. (previously presented) The bond pad of claim 12 further including a conductive tap region portion that is spaced apart from and surrounding the doped region, wherein the conductive tap region portion is decoupled from the supply voltage to provide a predetermined resistance between the doped region and the supply voltage.

17. (previously presented) The bond pad of claim 12 wherein the conductive tap region is a continuous region.

18. (previously presented) The bond pad of claim 17 wherein the conductive tap region completely surrounds the doped region.

19. (previously presented) The bond pad of claim 12 wherein the conductive tap region is a discontinuous region.

20. (previously presented) The bond pad of claim 19 wherein the conductive tap region substantially surrounds the doped region in a concentric-like manner.

21. (previously presented) The bond pad of claim 12 wherein the conductive region is polysilicon.

22. (previously presented) The bond pad of claim 21 wherein the conductive tap region is a doped layer positioned beneath the conductive region.

23. – 45. (cancelled)